

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	0	("(chlorine(chlorine near5 radical)Cl) near20(treat\$3 clean\$3 remov\$3) near20(hydrogen H2 "H.sub.2"))).PN.	US-PGPU B; USPAT; USOCR	OR	OFF	2005/02/18 12:28
L2	4705	(chlorine (chlorine near5 radical) Cl) near20 (treat\$3 clean\$3 remov\$3) near20 (hydrogen H2 "H.sub.2")	US-PGPU B; USPAT; USOCR	OR	ON	2005/02/18 13:31
L3	940	2 and titanium	US-PGPU B; USPAT; USOCR	OR	ON	2005/02/18 13:32
L4	92	3 and gate	US-PGPU B; USPAT; USOCR	OR	ON	2005/02/18 12:30
L5	84	4 and (source drain)	US-PGPU B; USPAT; USOCR	OR	ON	2005/02/18 13:34
L6	1016	(chlorine (chlorine near5 radical) Cl) near20 (treat\$3 clean\$3 remov\$3) near20 (hydrogen H2 "H.sub.2")	EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/02/18 13:30
L7	42	6 and titanium	EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/02/18 13:31
L8	173	(chlorine (chlorine near5 radical) Cl) near20 (treat\$3 clean\$3 remov\$3) near20 (UV (ultra near5 violet))	US-PGPU B; USPAT; USOCR	OR	ON	2005/02/18 14:49
L11	32	8 and titanium	US-PGPU B; USPAT; USOCR	OR	ON	2005/02/18 14:49
L12	50	8 and (Ti titanium)	US-PGPU B; USPAT; USOCR	OR	ON	2005/02/18 13:34
L13	36	12 and (source drain)	US-PGPU B; USPAT; USOCR	OR	ON	2005/02/18 13:34
L14	93	(chlorine (chlorine near5 radical) Cl) near20 (treat\$3 clean\$3 remov\$3) near20 (UV (ultra near5 violet))	EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/02/18 14:50
L15	0	14 and titanium	EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/02/18 14:50

L16	11	14 and (semiconducutor substrate wafer)	EPO; JPO; DERWENT ; IBM_TDB	OR	ON	2005/02/18 14:51
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